

Amendments to the Claims:

Claims 1- 6 (Canceled).

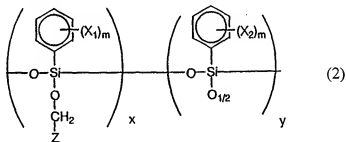
7. (Currently amended) A method of forming a polymer optical waveguide pattern, comprising the steps of:

forming a core layer of a photosensitive composition by a spin-coating method with a thickness which satisfies a single-mode condition of a resulting optical waveguide that comprises the core layer;

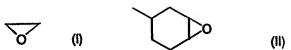
~~applying and drying~~ [[a]] the photosensitive composition for optical waveguides;
irradiating said resultant photosensitive composition thin film for optical waveguides with light through a mask; and

directly forming a core-ridge pattern by wet etching said photosensitive composition thin film;

wherein the photosensitive composition for optical waveguides comprises an organic oligomer and a polymerization initiator, said organic oligomer being a silicone oligomer represented by the following formula (2):



wherein X₁ and X₂ may be the same as or different from each other, and denote hydrogen, deuterium, halogen, an alkyl group or an alkoxy group; m is an integer from 1 to 5; x and y designate the proportion of respective units, and y is smaller than x and may be 0; and Z denotes an epoxy group shown in the following formula (I) or (II):



Appl. No.: 10/803,446
Amdt. dated March 13, 2007
Reply to Official Action of November 13, 2006

Claims 8- 20 (Canceled).